Amendments to and listing of the claims:

Please amend claim 1 and delete claims 3, 5, and 6 so that the claims read as follows:

1. (Currently Amended) A resin composition for stereolithography, which is an actinic radiation-curable resin composition comprising:

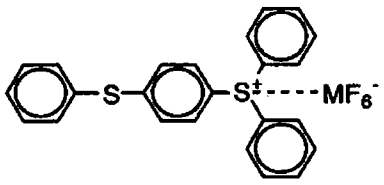
a cationic-polymerizable organic compound comprising at least one compound having an epoxy group;

a radical-polymerizable organic compound comprising at least one compound having a (meth)acryl group;

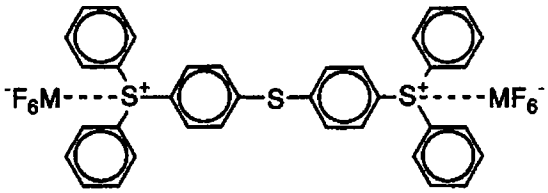
a photo initiator for cationic polymerization; and

an ultraviolet light-sensitive photo initiator for radical polymerization,

wherein the photo initiator for cationic polymerization comprises a compound represented by the following formula (I), the compound having a purity of 97% or higher and containing less than 3% by mass of a compound represented by the following formula (II):



…(I)



…(II)

wherein M represents an antimony atom ~~or a phosphorus atom~~; and the broken line between S^+ and MF_6^- represents an ionic bond.

2. (Canceled)

3. (canceled)

4. (Canceled)

5. (canceled)

6. (canceled)

7. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, which comprises an oxetane compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.

8. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, which comprises a polyalkylene ether compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.

9. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, wherein a concentration of diphenyl sulfoxide in the compound represented by formula (I) is less than 0.05% by mass.

10. (Previously Presented) The resin composition for stereolithography as claimed in claim 1, wherein the photo initiator for cationic polymerization contains substantially no compound represented by formula (II).